

ABSTRACT

Disclosed herein are a positive-type photoresist which can be developed with an aqueous alkali solution of low concentration or neutral water, can be readily stripped with
5 ozone water, hardly produces scum, and contributes to reduction in costs and environmental loads, and a method for manufacturing a structure having a circuit formed using a resist pattern of the photoresist.

A positive-type photoresist comprising a novolac resin
10 having a benzene nucleus to which two or more hydroxyl groups are bonded and a weight-average molecular weight of 1,000 to 20,000. A method for manufacturing a structure having a circuit formed using as a resist pattern the positive-type photoresist comprising the steps of forming a resist film on the surface
15 of a substrate by the use of the positive-type photoresist, exposing the resist film to light and carrying out development, forming a circuit using the resist pattern, and removing the resist film.